

Investigation of near-critical foam targets for laser-driven ion acceleration



Irene Prencipe
6th Target Fabrication Workshop
Greenwich, May 2017



HZDR

HELMHOLTZ
ZENTRUM DRESDEN
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NanoLab

Nanolab @ Politecnico di Milano

- Advanced targets for laser driven ion sources
- Target fab, PIC, experiments
- Beamline application: material science



ERC-2014-CoG
No. 647554

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Laser-particle acceleration group

- DRACO 150 TW/1 PW (Ti:Sapphire, 30 fs)
- Beamline application: cancer therapy (soon in vivo)

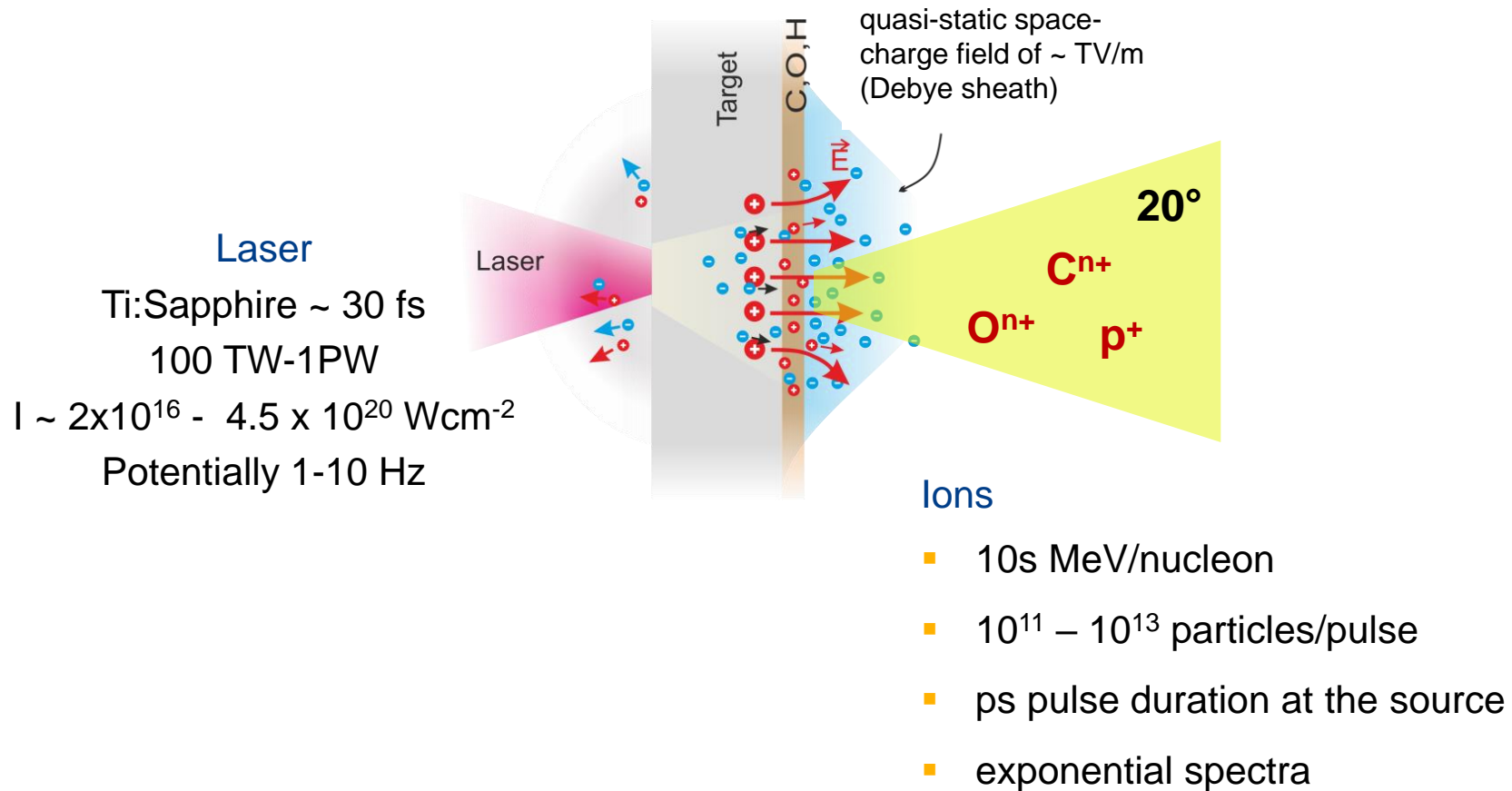
HZDR High Energy Density group

- HI/HE lasers @ European XFEL
- fs probing of laser-driven plasmas on the few nm scale by Small Angle X-Ray Scattering

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Access to the characterization capabilities of the
Institute of Ion Beam Physics and Material Research

Target Normal Sheath Acceleration (TNSA)

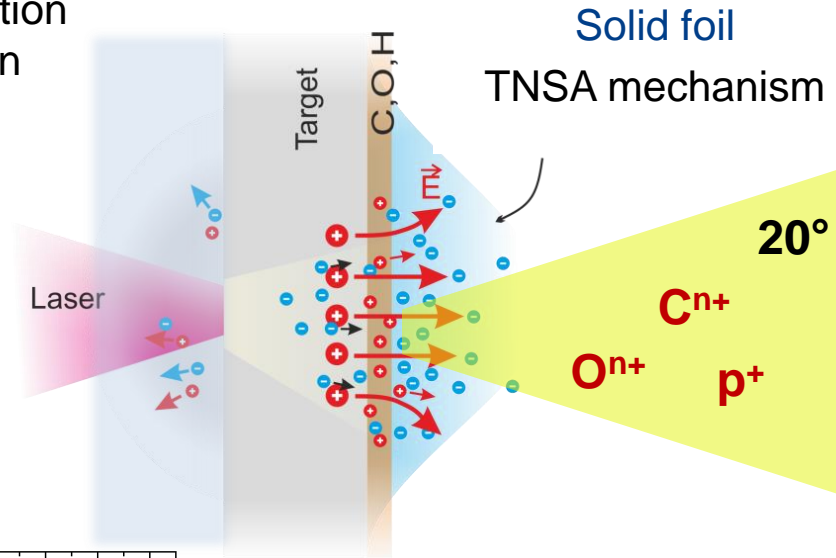


A. Macchi et al., Rev. Mod. Phys., **85** 751 (2013)

Enhanced laser absorption in near-critical layer

Low-density layer

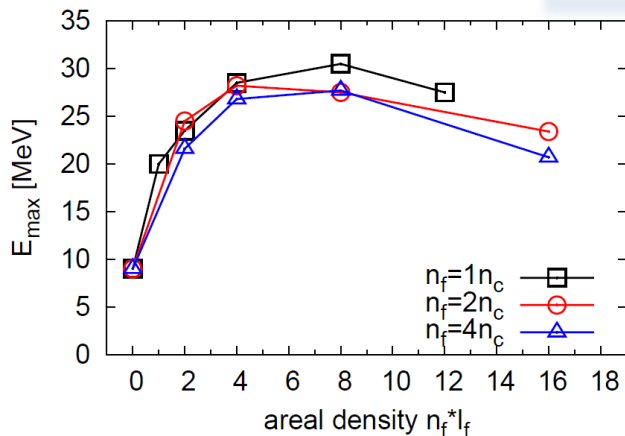
Increased absorption
and hot electron
generation



2D PIC simulations

Density $\sim n_c$

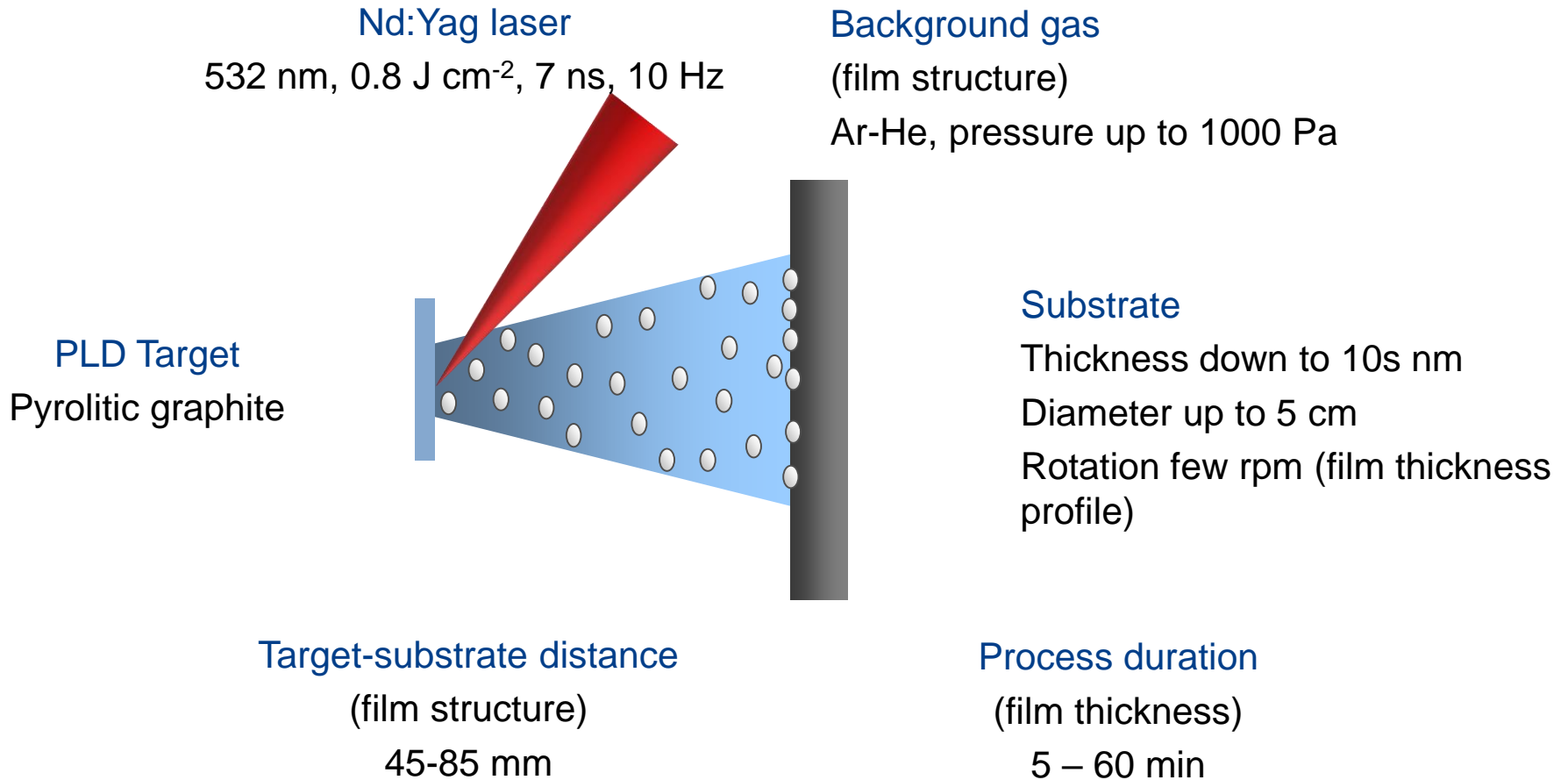
Thickness $\sim 10 \mu\text{m}$



Mass density $\sim 5.7 \text{ mg/cm}^3$ for C^{6+} , $\lambda=800 \text{ nm}$
(graphite density $\approx 2 \text{ g/cm}^3$)

T. Nakamura *et al.*, Phys. Plasmas, **17** 113107 (2010)
A. Sgattoni *et al.*, Phys. Rev. E, **85** 036405 (2012)
J. H. Bin, Phys. Rev. Lett., **115** 064801 (2016)

ns Pulsed Laser Deposition (PLD) in background gas



ns Pulsed Laser Deposition (PLD) in background gas



Low pressure
High kinetic energy
Atom-by-atom
deposition

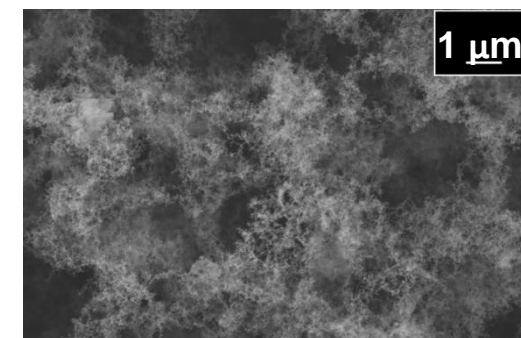
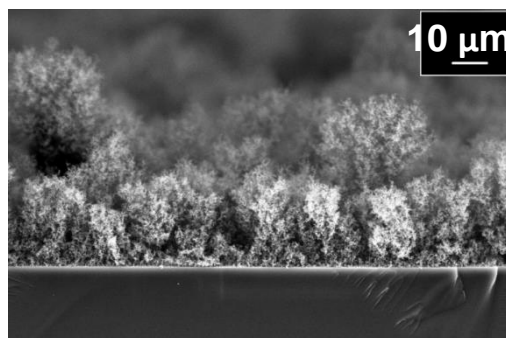
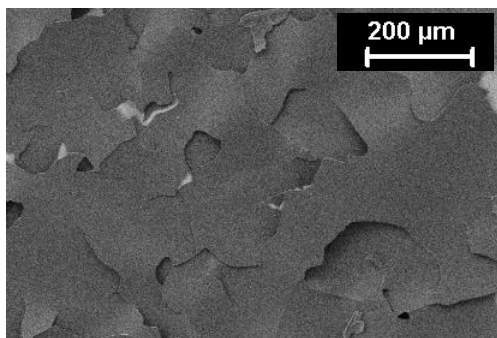
Vacuum

Pressure

High pressure
Low kinetic energy
Cluster formation

Ar 30 Pa

Ar 150 Pa



A. Bailini *et al.*, Appl. Surf. Sci., **253** 8130 (2007); A. Zani *et al.*, Carbon, **56** 358 (2013)

ns Pulsed Laser Deposition (PLD) in background gas

Density gradient

Obtained by linear increase of background pressure (100 Pa to 700 Pa)

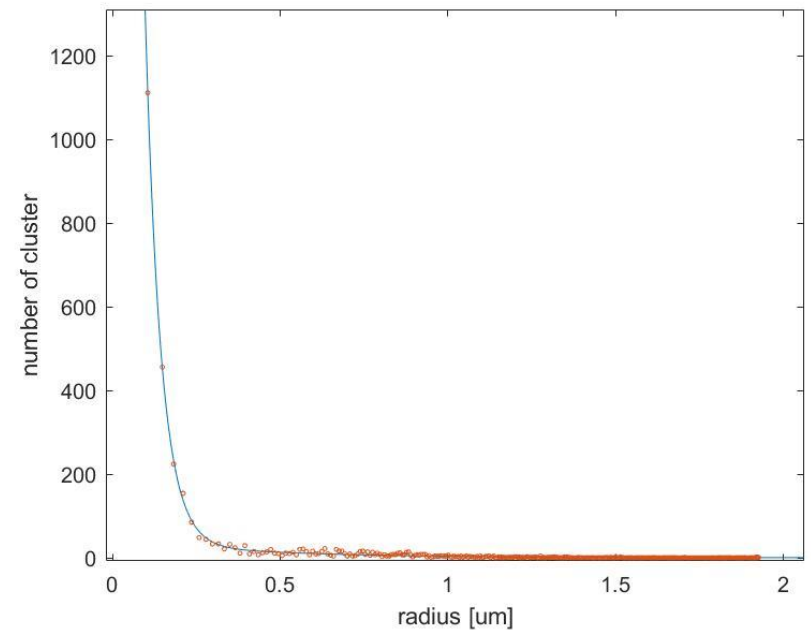
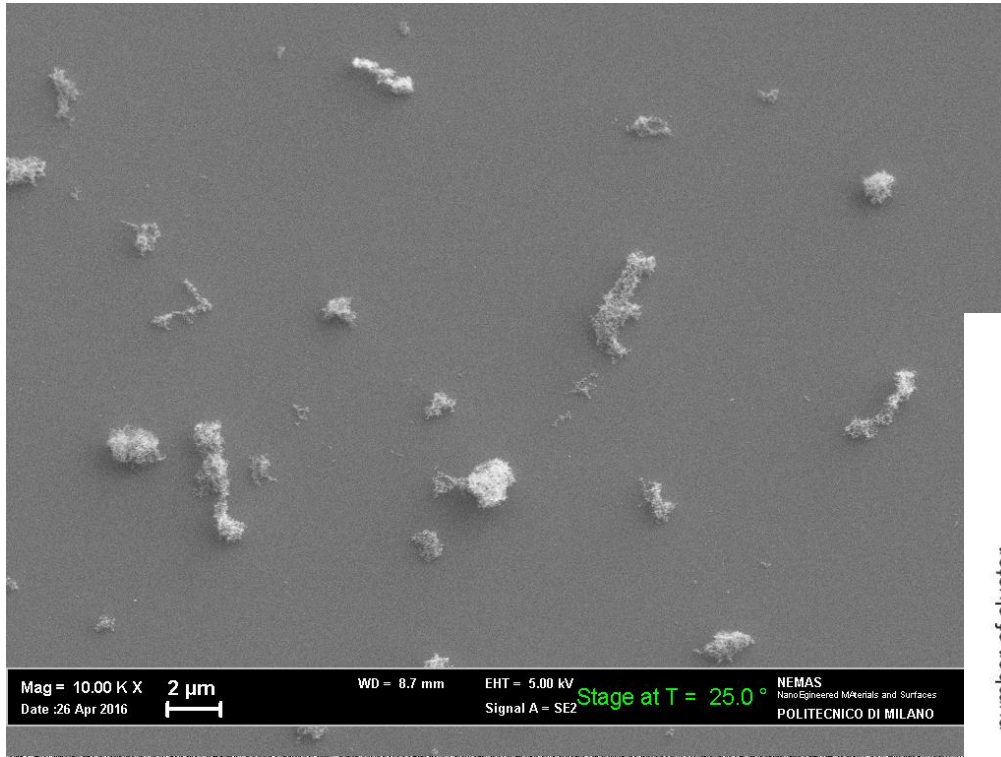


$\sim 10 \text{ mg/cm}^3$

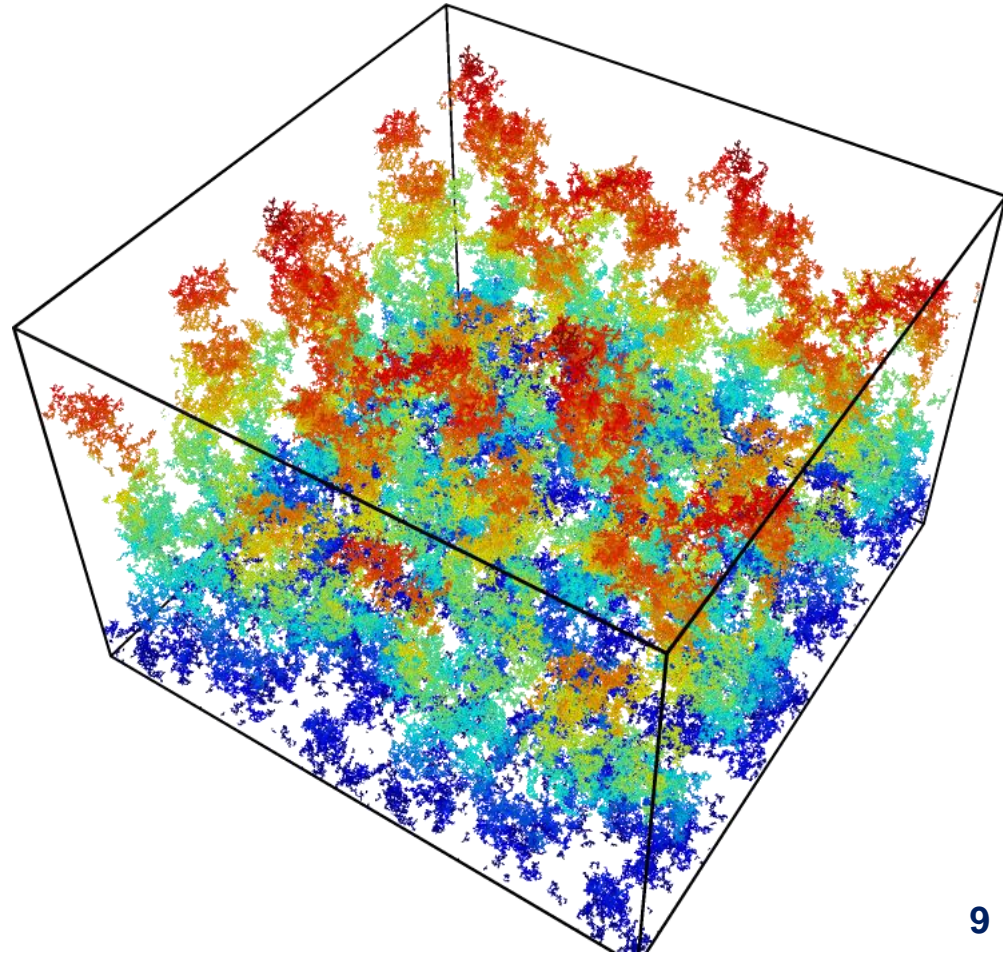
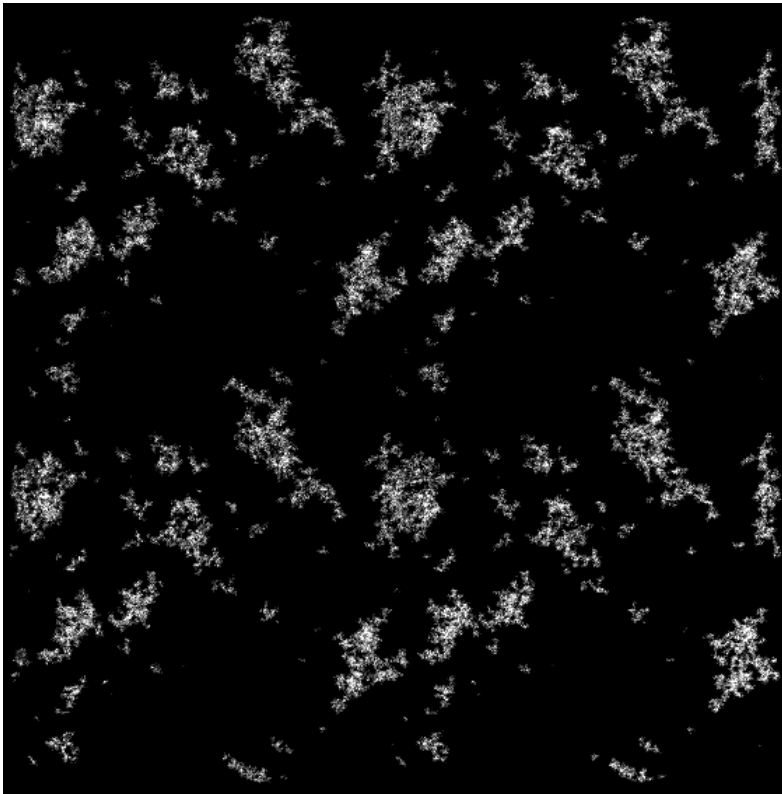
$\sim 150 \text{ mg/cm}^3$

Ar, $\lambda = 532 \text{ nm}$, $E = 150 \text{ mJ}$, Substrate-Target distance = 4.5 cm

Diffusion limited cluster-cluster aggregation model for foam deposition

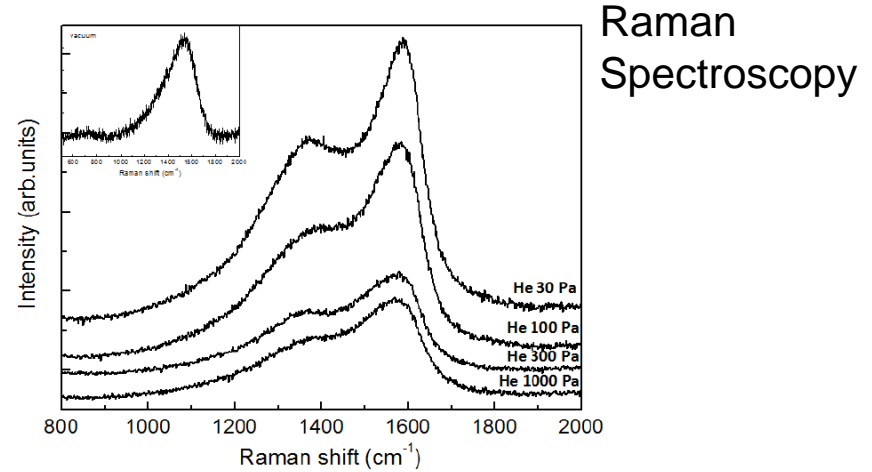
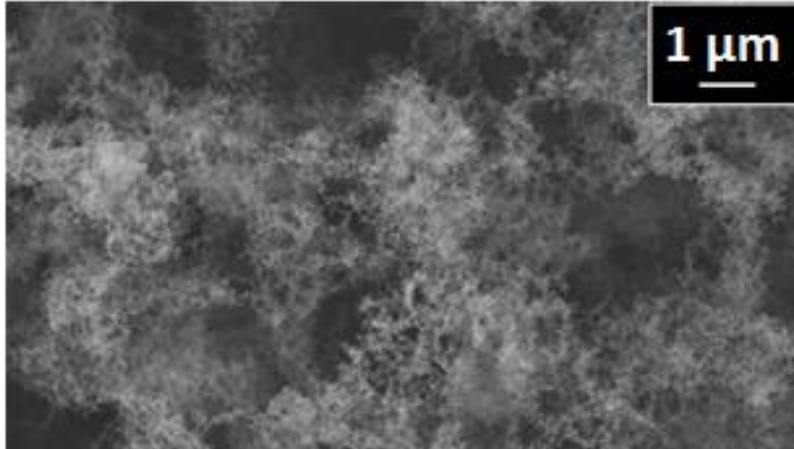


Diffusion limited cluster-cluster aggregation model for foam deposition



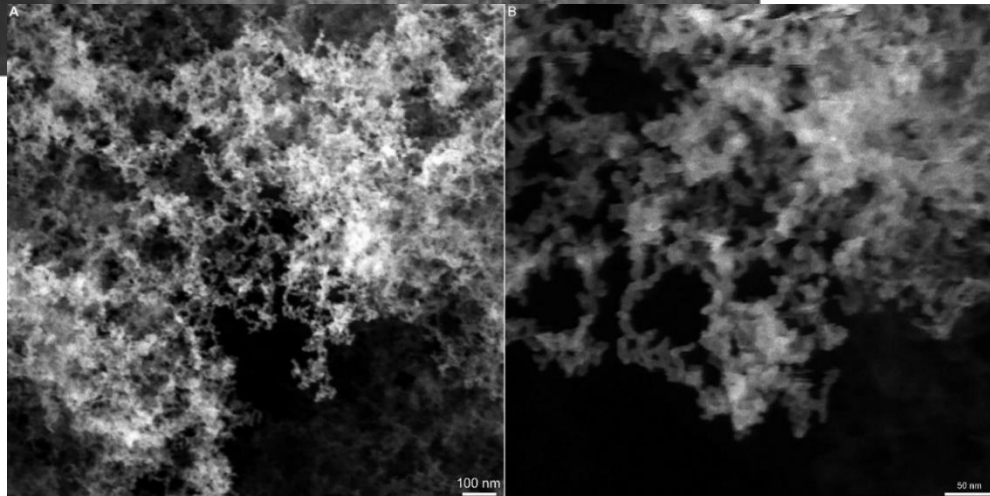
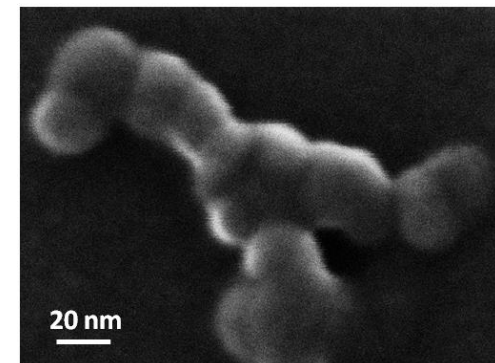
Morphology and nanostructure

Scanning Electron Microscopy



Raman Spectroscopy

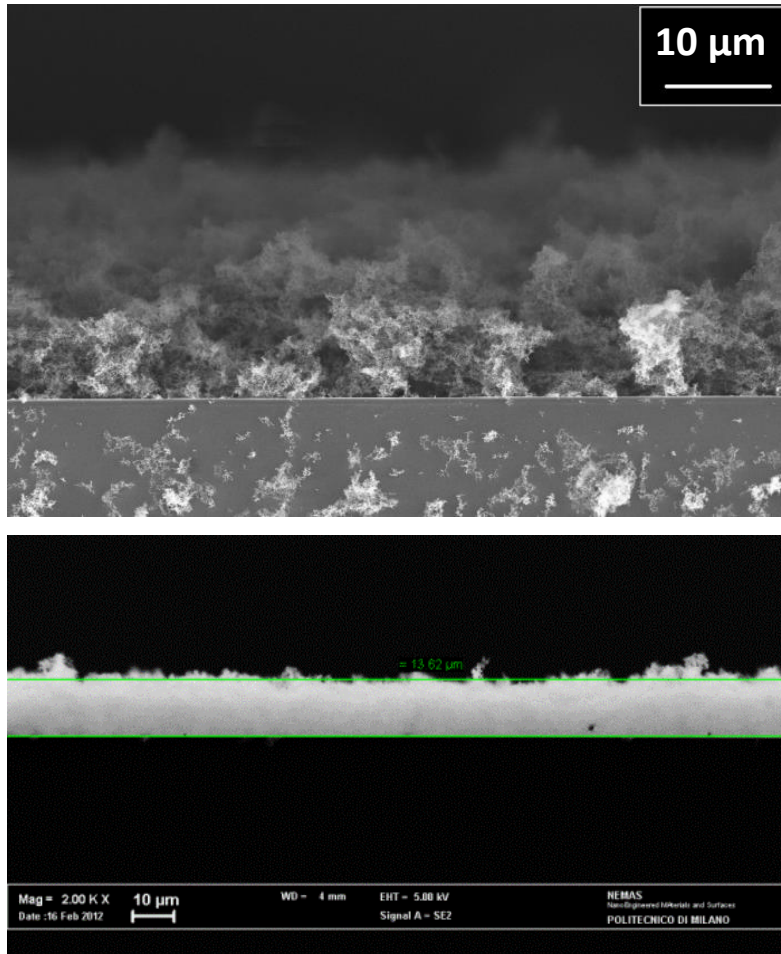
Scanning Transmission Electron Microscopy



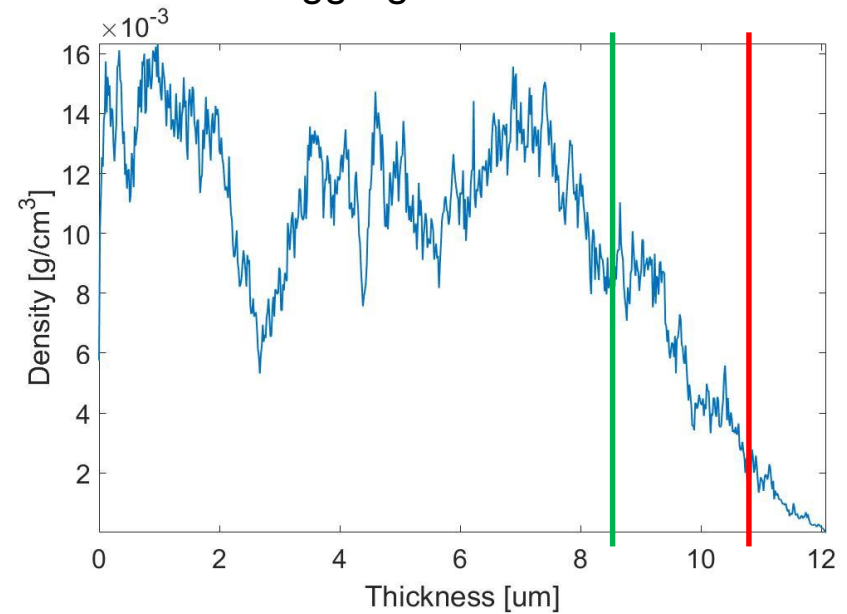
He Ion Microscopy @ IBC-HZDR

Thickness

Cross Section Scanning Electron Microscopy



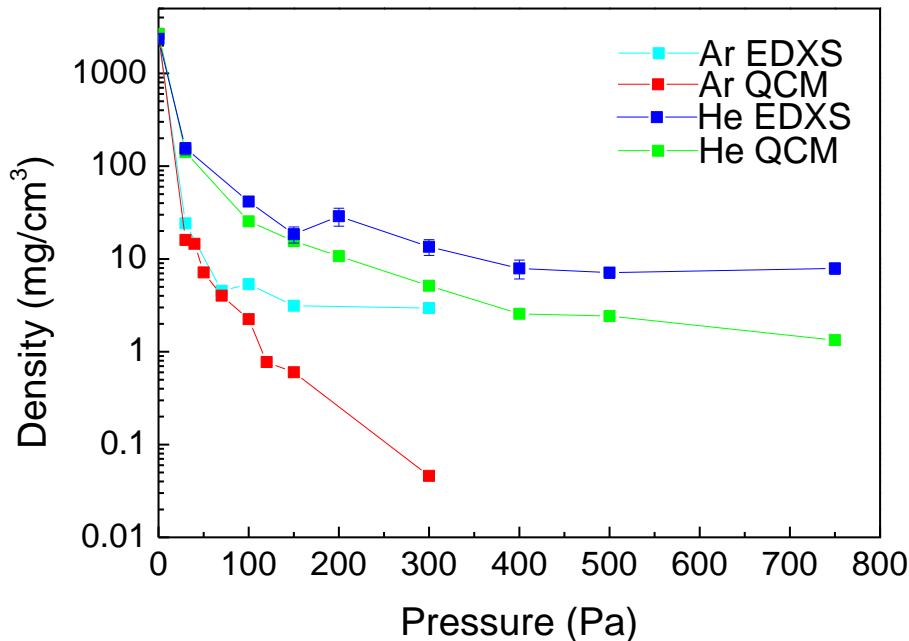
Diffusion limited cluster-cluster aggregation model



Film thickness ~ 4 μm – 80 μm

Density and composition

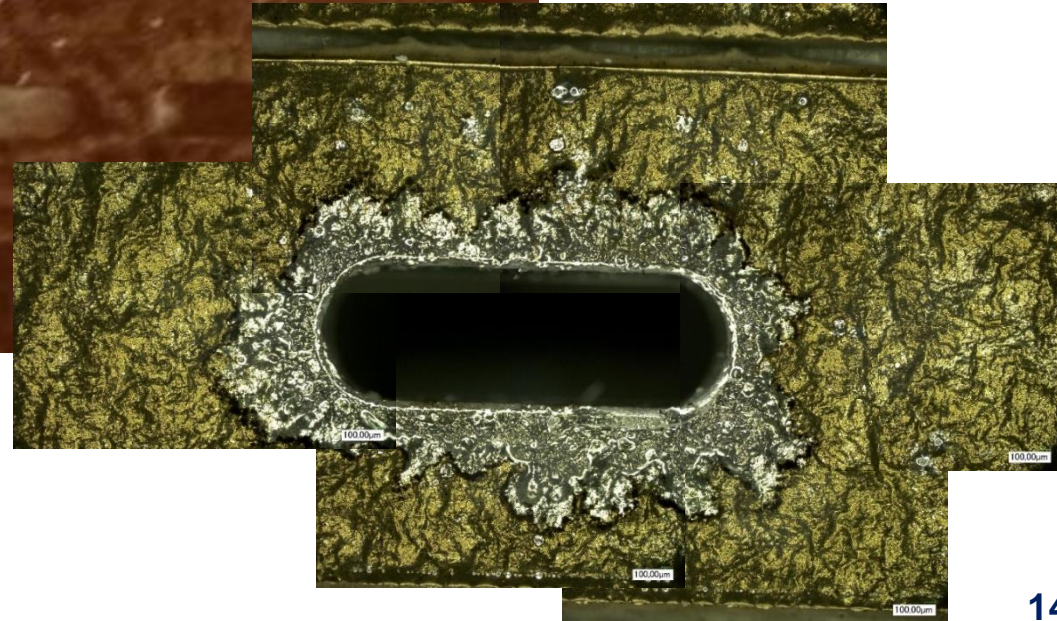
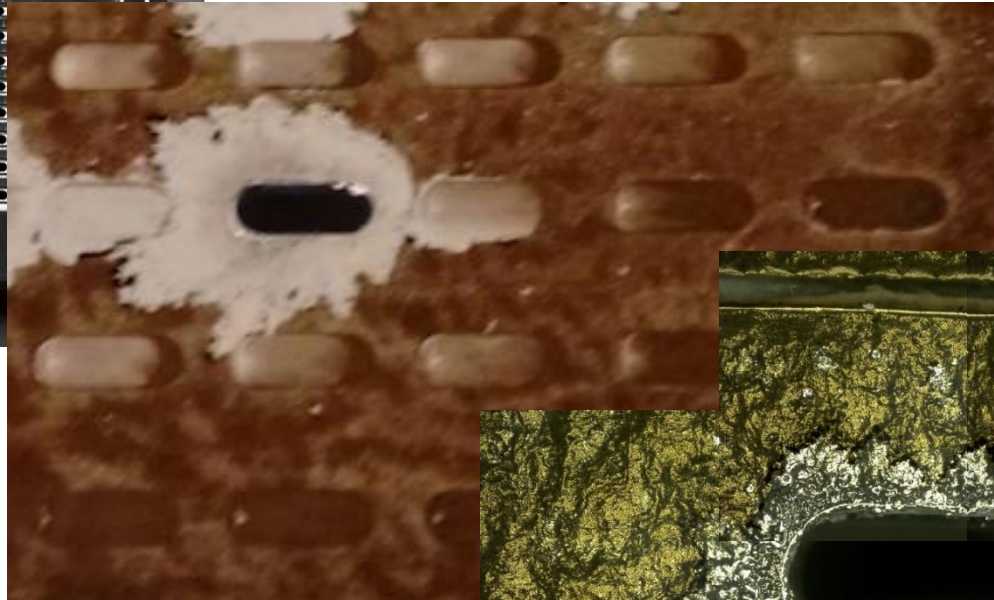
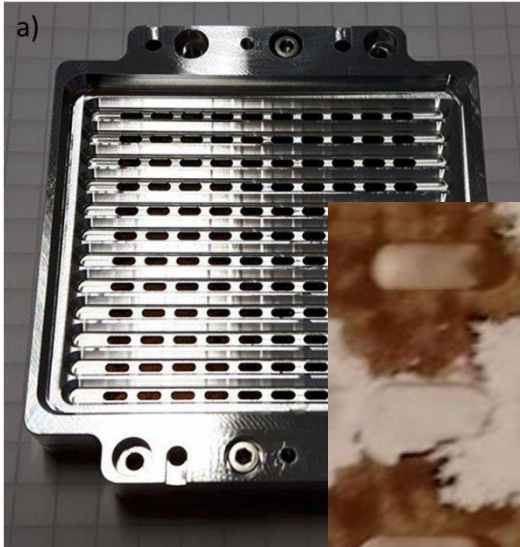
Quartz Crystal Microbalance
vs Energy Dispersive X-Ray Spectroscopy



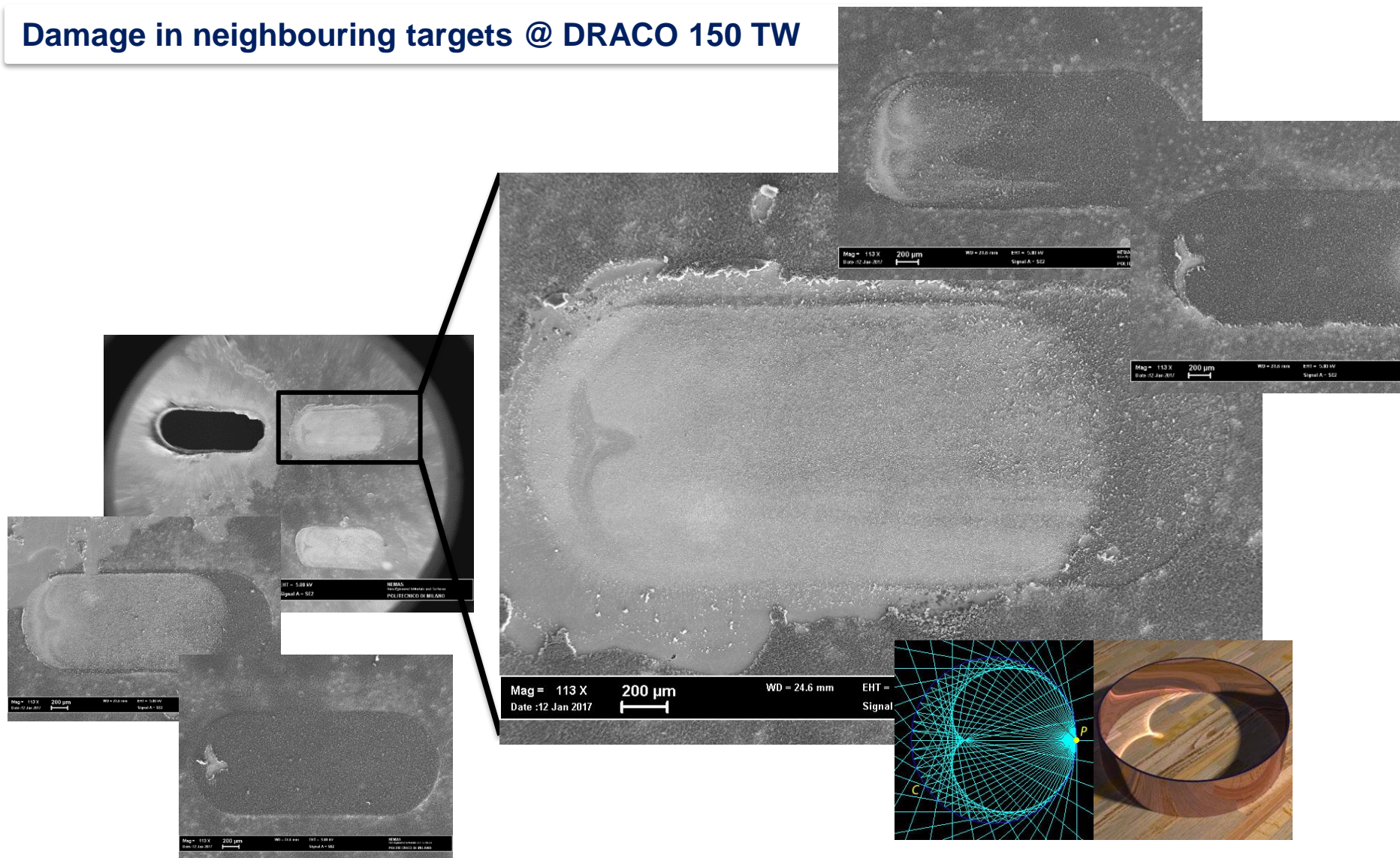
Ion Beam Analysis (NRA and ERDA)
@ IBC-HZDR

- Density benchmark
 $\rho_{\text{IBA}} \sim 13 \text{ mgcm}^{-3}$ vs $\rho_{\text{EDS}} \sim 12 \text{ mgcm}^{-3}$
- Composition
 - C ~ 92 at.%
 - H ~ 6.3 +/- 2 at.%
 - N < 0.4 (~0.2) at.%
 - O ~ 1.3 at.%

Damage in neighbouring targets @ DRACO 150 TW



Damage in neighbouring targets @ DRACO 150 TW



3 Experimental campaigns

Ti:Sapphire lasers, ~ 30 fs, $\lambda=800$ nm, $I \sim 10^{16}$ - $4.5 \cdot 10^{20}$ W/cm²



UHI100-CEA Saclay,
France (2012)



PROOF OF CONCEPT



CoReLs-GIST 1 PW,
South Korea
(2014-15)



PARAMETRIC SCANS



DRACO 150 TW,
HZDR, Germany
(2017)



ADDITIONAL DIAGNOSTICS

M. Passoni *et al.*, Plasma Phys. Control. Fusion, **56** 045001 (2014)

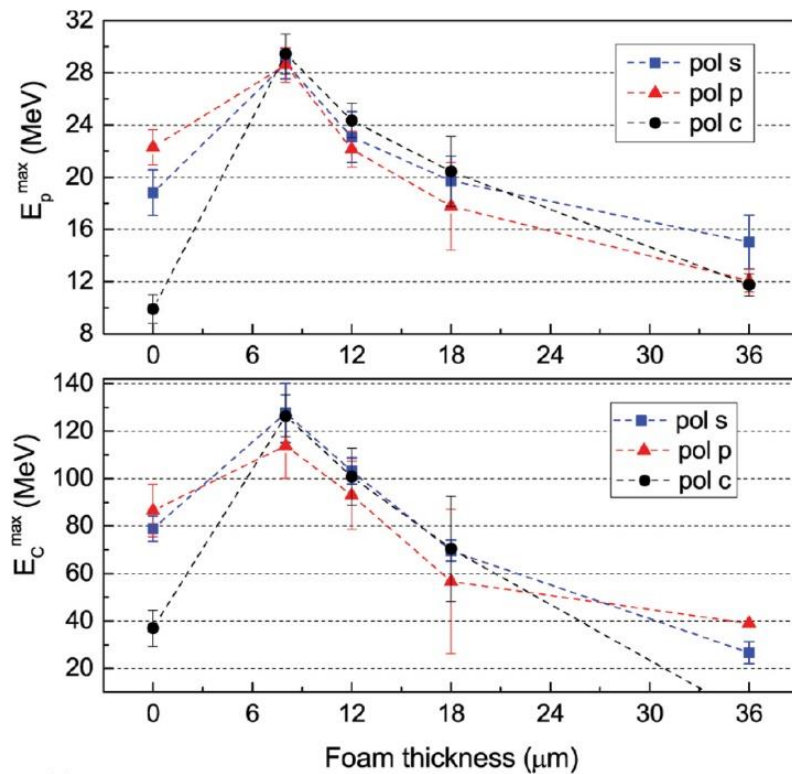
I. Prencipe *et al.*, Plasma Phys. Control. Fusion, **58** 034019 (2016)

M. Passoni *et al.*, Phys. Rev. Acc. Beams, **19** 061301 (2016)

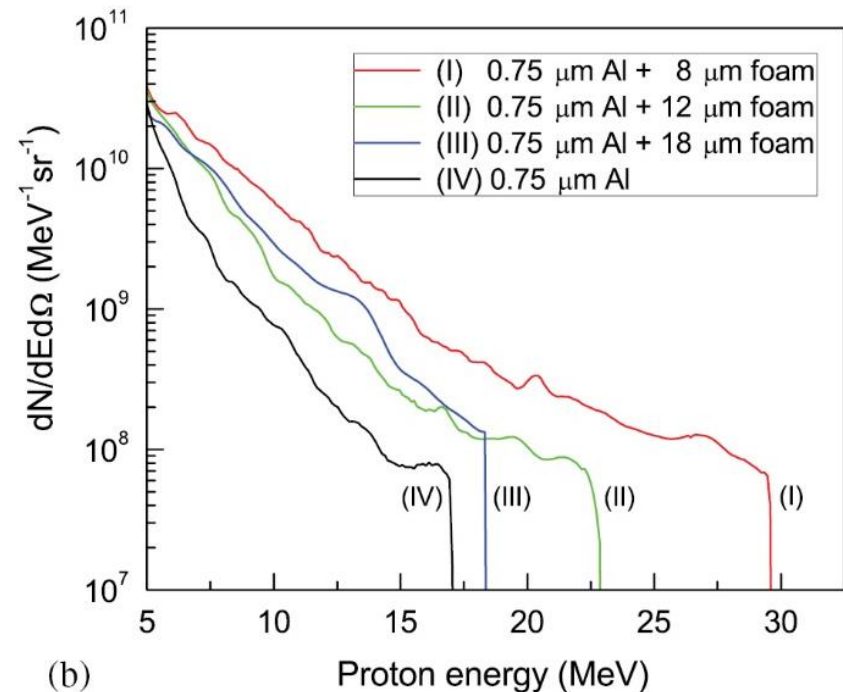
Results

Enhanced TNSA (cut-off energy, ion number)

- FOR optimal foam properties
- Reduced dependence on substrate thickness



(a)

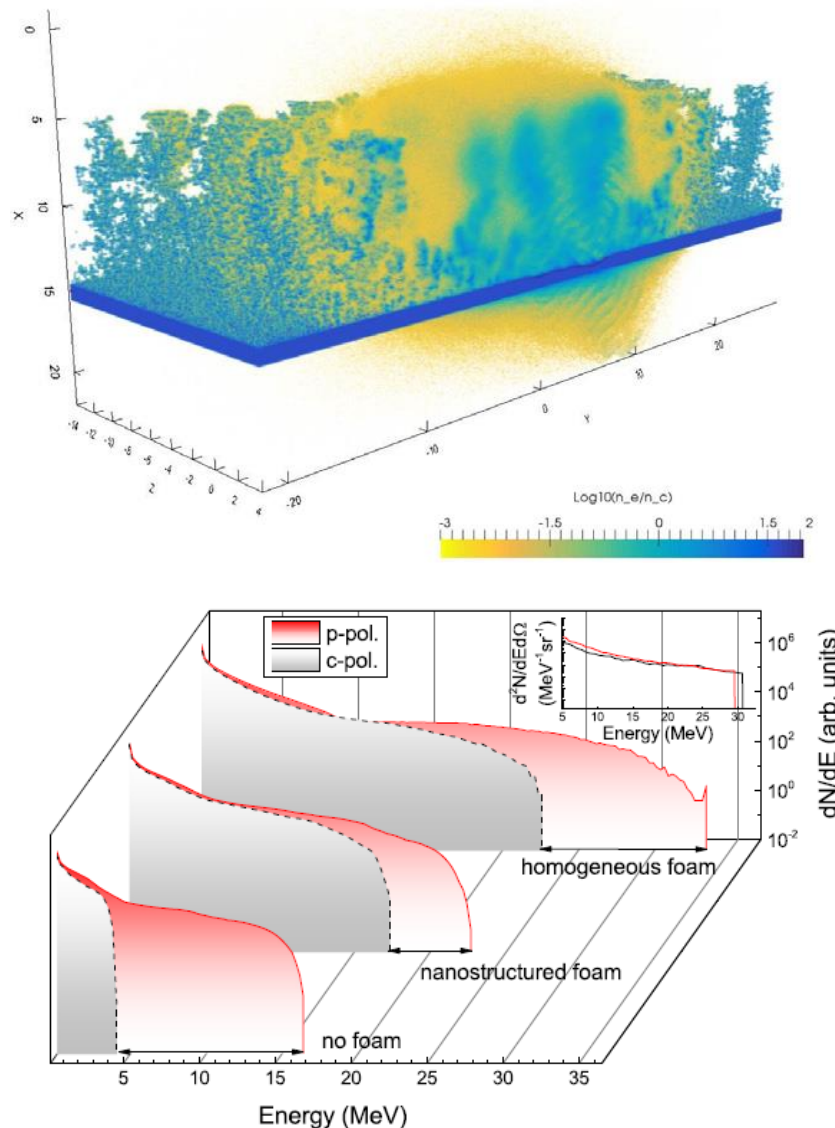
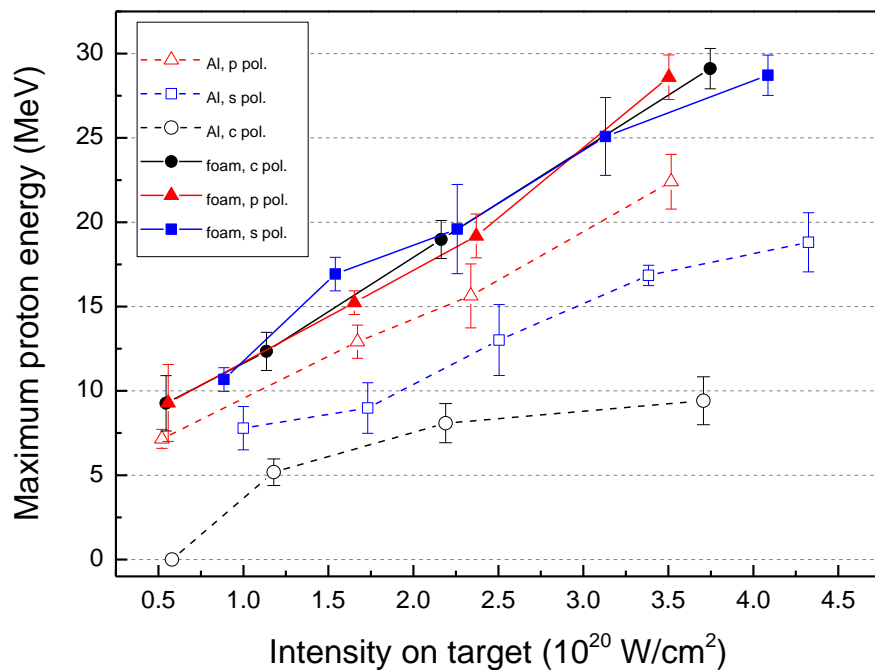


(b)

Results

Effect of foam nanostructure

- Reduced dependence on polarization



- **Target production**
 - C foam coating by ns Pulsed Laser Deposition
 - 4-80 μm , down to 7 mg/cm³
- **Target characterization**
 - SEM, EDS, QCM, STEM, Raman @ Politecnico di Milano
 - He microscopy, ERDA, NRA @ HZDR
- **Study of target damage @ DRACO, HZDR**
- **Experimental results**
 - TNSA enhancement and foam optimization
 - Role of nanostructure (3D PIC simulations)



NanoLab

M. Passoni, A. Pazzaglia, D. Dellasega, A. Maffini, V. Russo, L. Fedeli...



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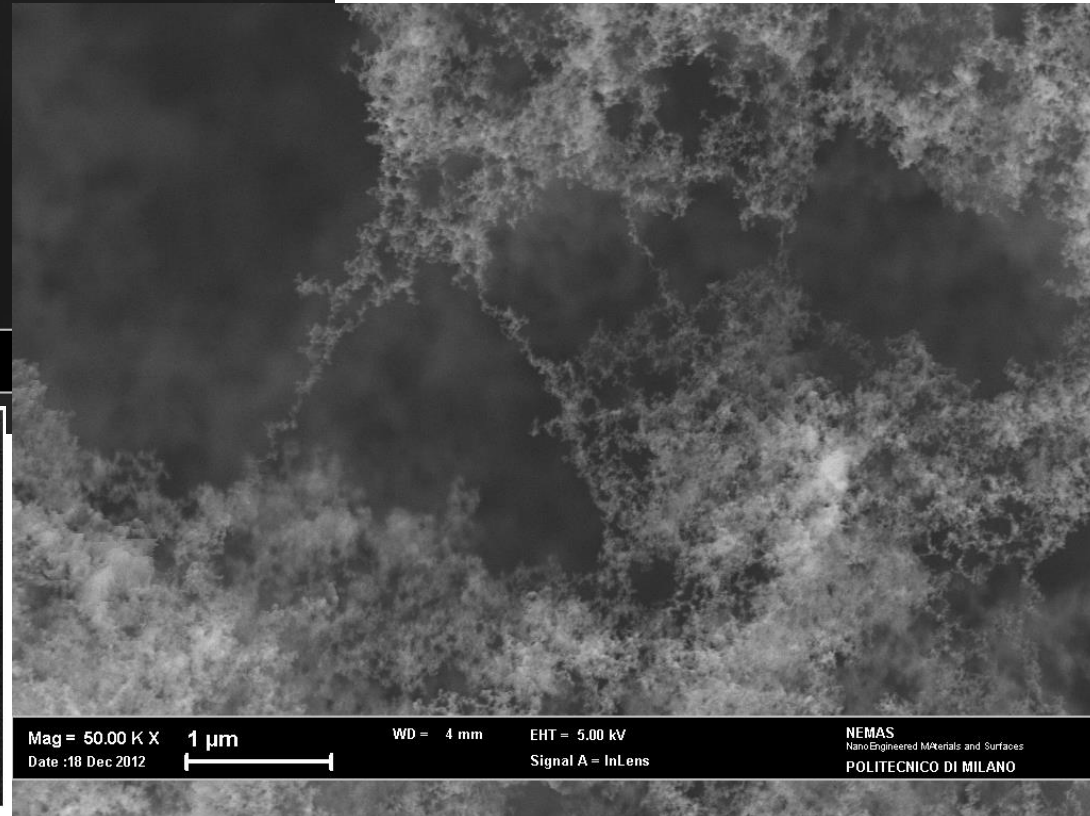
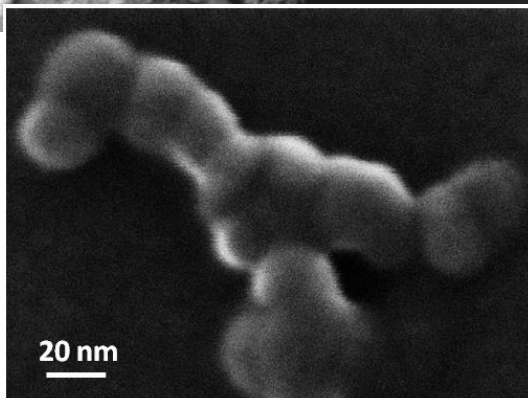
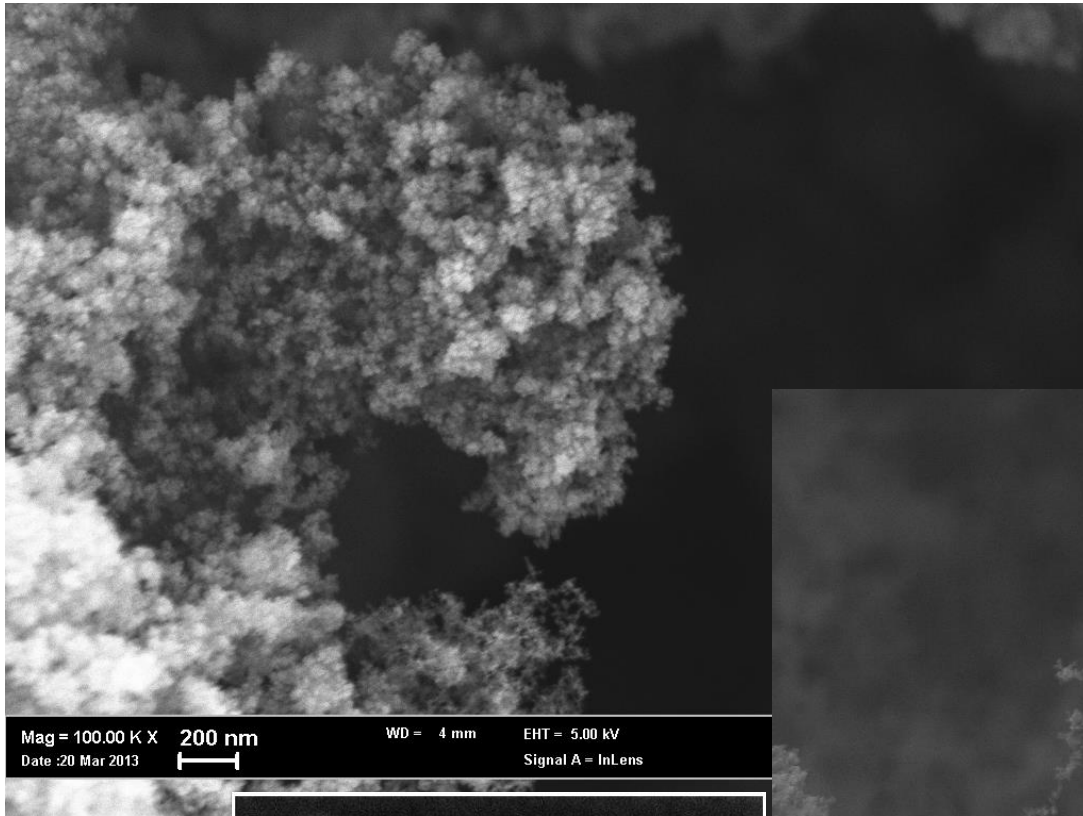
U. Schramm, J. Metzkes, K. Zeil,
S. Kraft, L. Obst, M. Rehwaldt, M.
Sobiella...

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T. Cowan, A. Laso Garcia,
T. Kluge, M. Molodtsova,
A. Ferrari...

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J. Von Borany, J. Grenzer,
G. Hlawacek, J. Julin, R. Heller

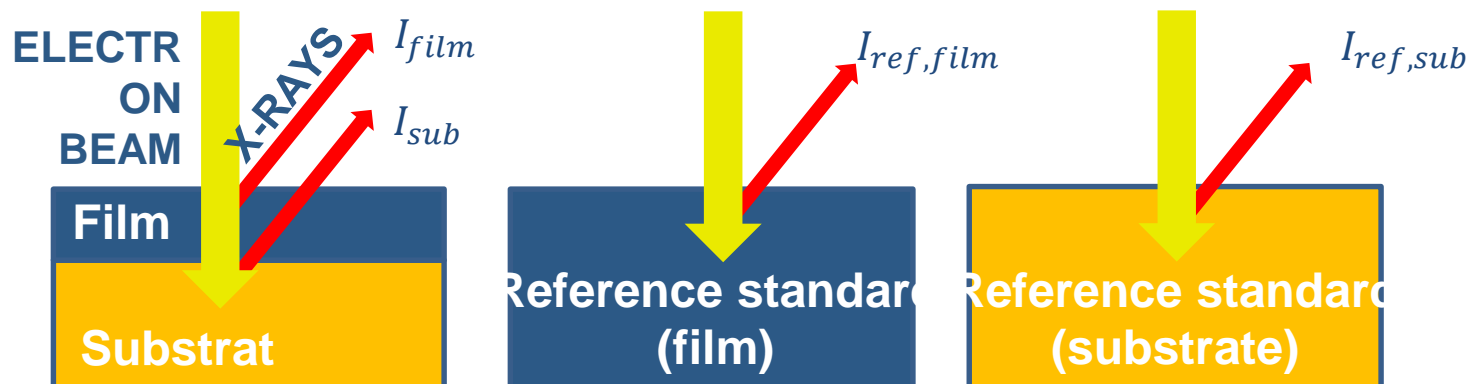


Key features	
Bandwidth $\Delta E/E$	10^{-3} (natural FEL source) and 10^{-4} (standard monochromator, seeding); 10^{-6} * (high-resolution monochromator)
Photon energy range	3–5 keV**, 5–20 keV, 20–25 keV**
Polarization	Linear (horizontal) Circular (future option)
Pulse duration	2–100 fs FWHM
Beam size	Sub- μm to > 100 μm (provided by various compound refractive lens stages) >mm unfocused
Special optics	Split and delay line (<i>BMBF contribution</i>) High-resolution monochromator
Optical lasers	High-energy (100 J-class) long pulse (>ns) laser (<i>HIBEF contribution</i>) High-intensity (100 TW-class) short pulse (~30 fs) laser (<i>HIBEF contribution</i>) Pump–probe (mJ to 100 mJ class) short pulse (~15 fs – 1 ps) laser

⁻⁶
* 10^{-6} bandwidth only for a few selected photon energies

**Limited in terms of focusing capability, available photon number of sample, quantum efficiency of detectors

Energy Dispersive X-Ray Spectroscopy (EDS)



TWO APPROACHES FOR AREAL DENSITY CALCULATION



$$\frac{I_{film}}{I_{ref,film}} = f(\rho z)$$

COATING METHOD



$$\frac{I_{sub}}{I_{ref,sub}} = g(\rho z)$$

SUBSTRATE METHOD

**CONVENTIONALLY:
THICKNESS MEASUREMENT FOR
COMPACT FILMS WITH KNOWN
DENSITY**



**DENSITY MEASUREMENT
OF NANOSTRUCTURED FILMS
IN A WIDE DENSITY RANGE**